

Single-electron regime and Pauli Spin Blockade in a silicon MOS DQD

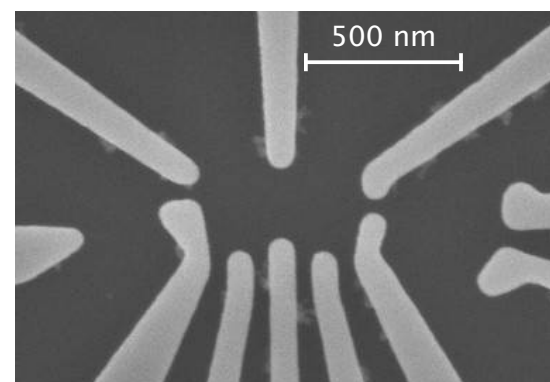
Outline

Sophie Rochette¹,

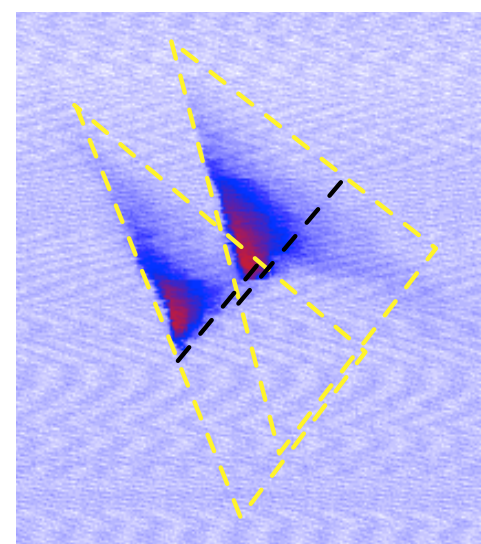
Gregory A. Ten Eyck², Tammy Pluym²,
Michael P. Lilly², Malcolm S. Carroll²,
and Michel Pioro-Ladrière¹.



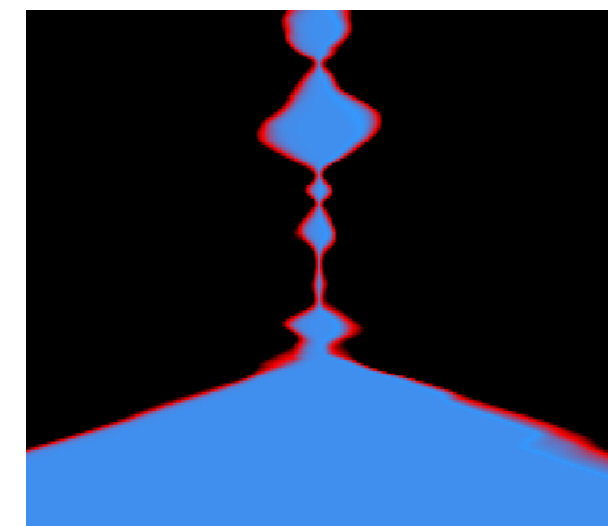
Si MOS DQD



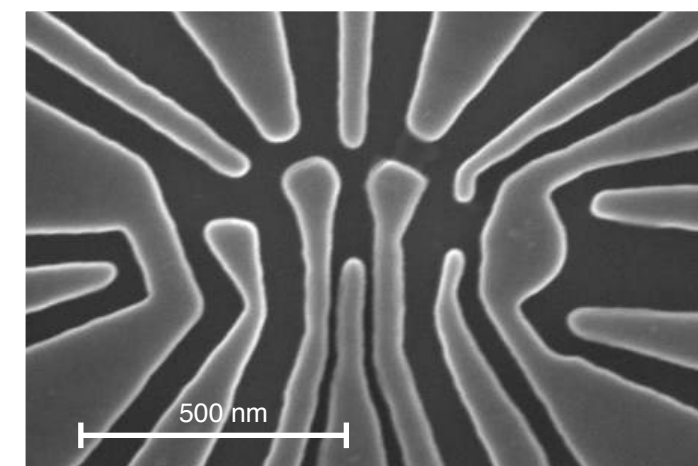
Spin Blockade



Single electron regime

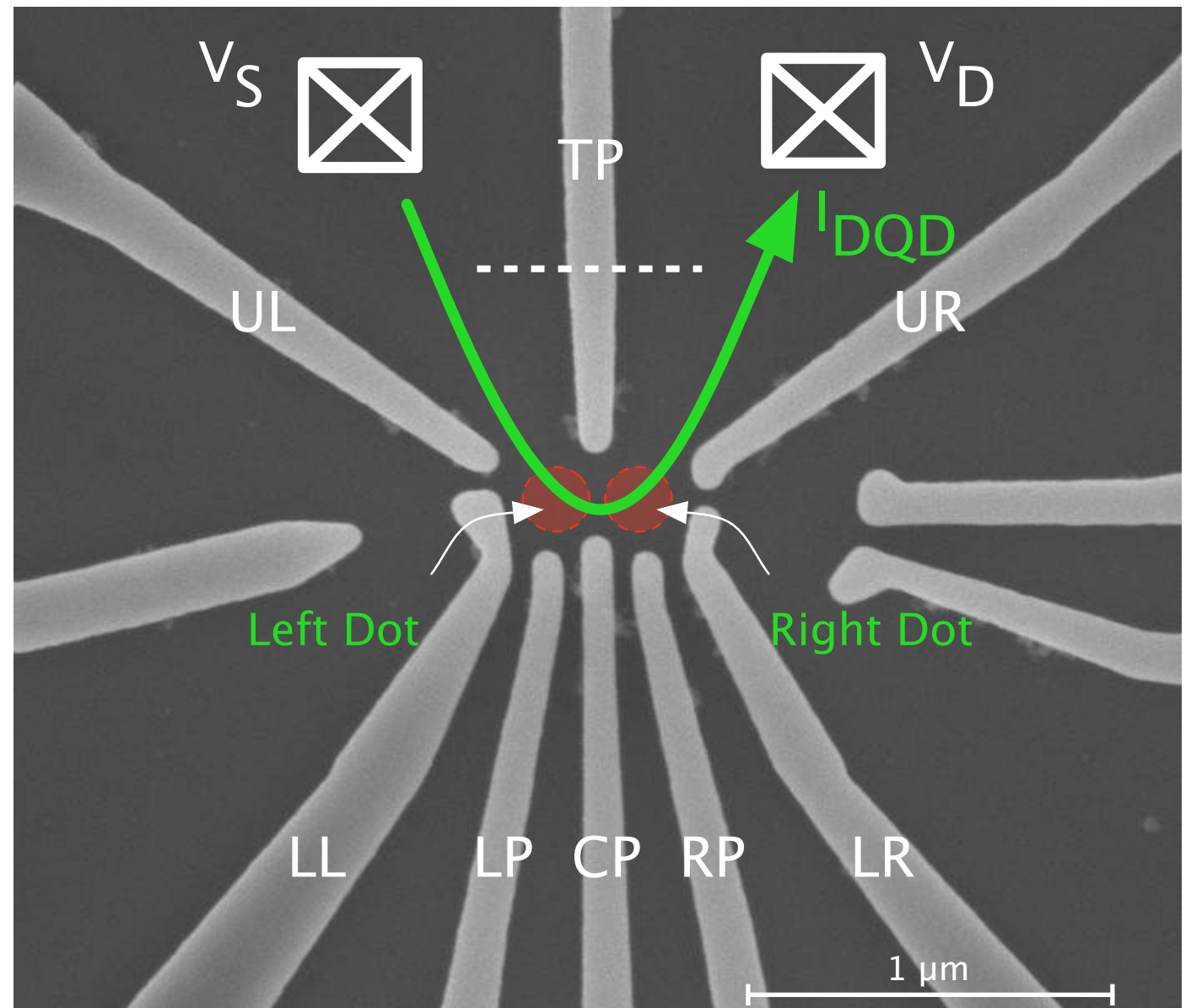
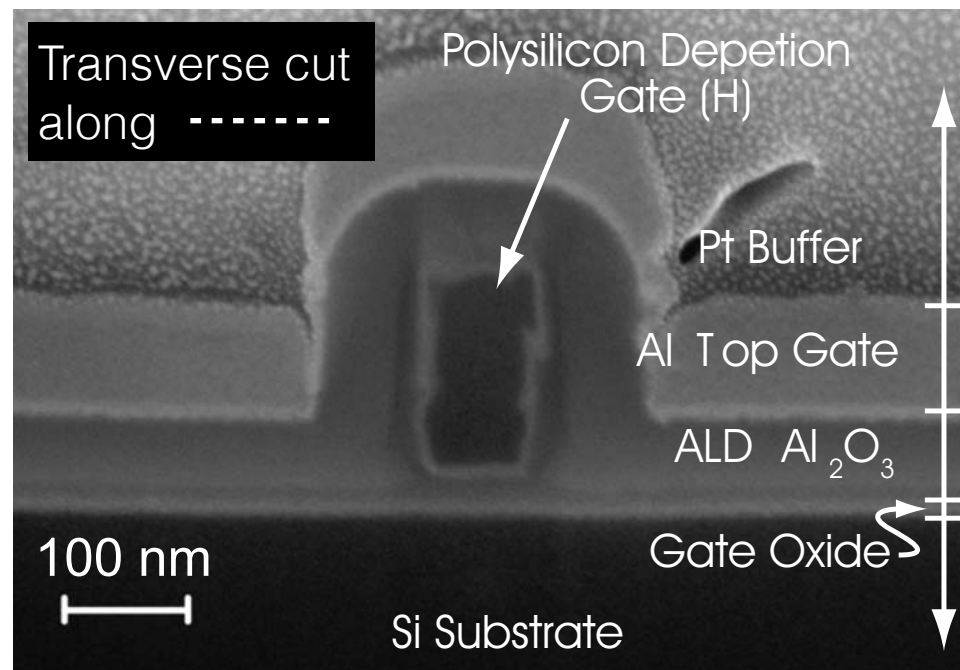


New design: All Si

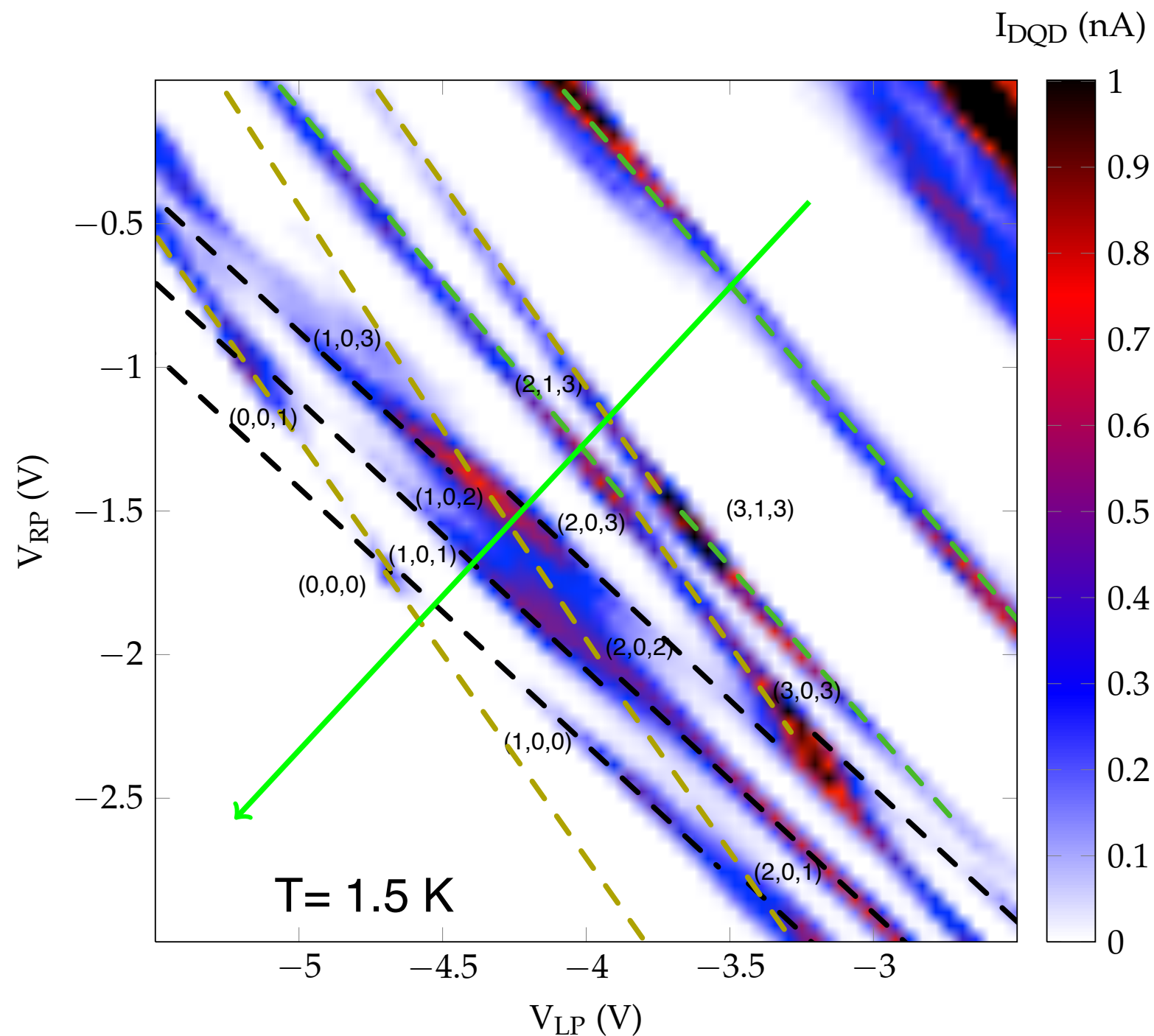


Device

- Si MOS DQD
- Poly-Si depletion gates
- Aluminium Accumulation Gate
- Transport measurements

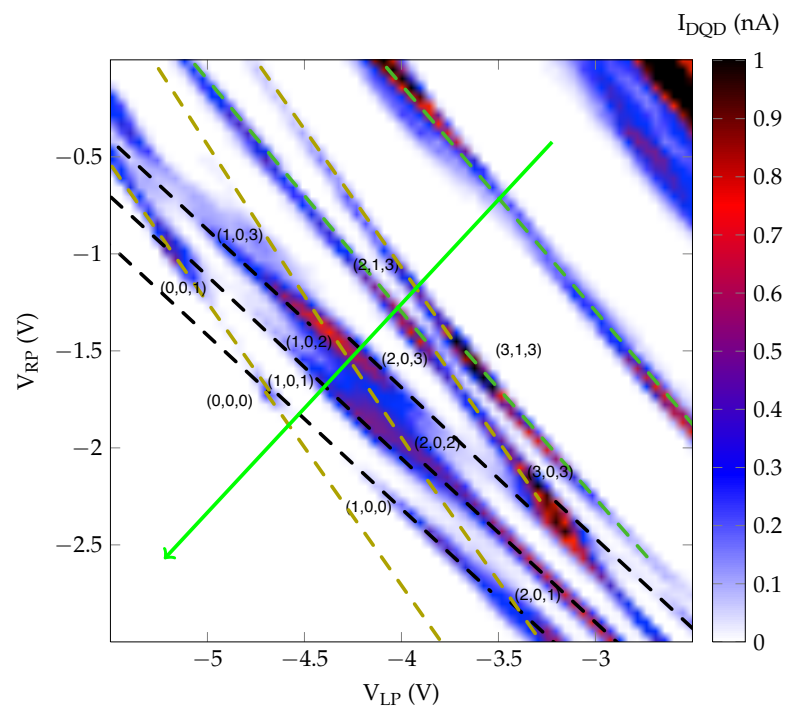


Stability Diagram

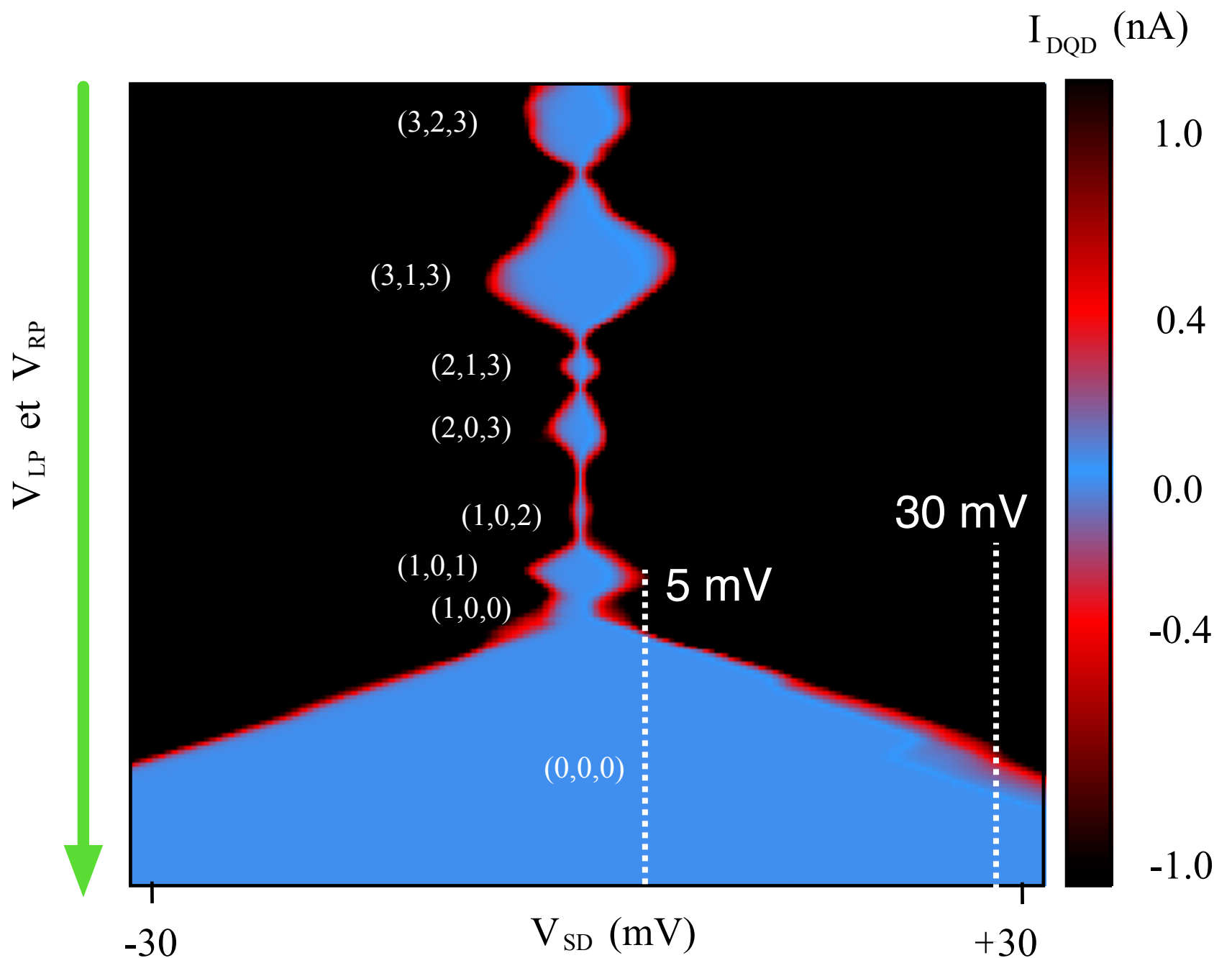


- $T = 1.5$ K
- Rough tuning
- Tendancy to triple dot formation
- No current region: emptied dots?

Coulomb Diamonds



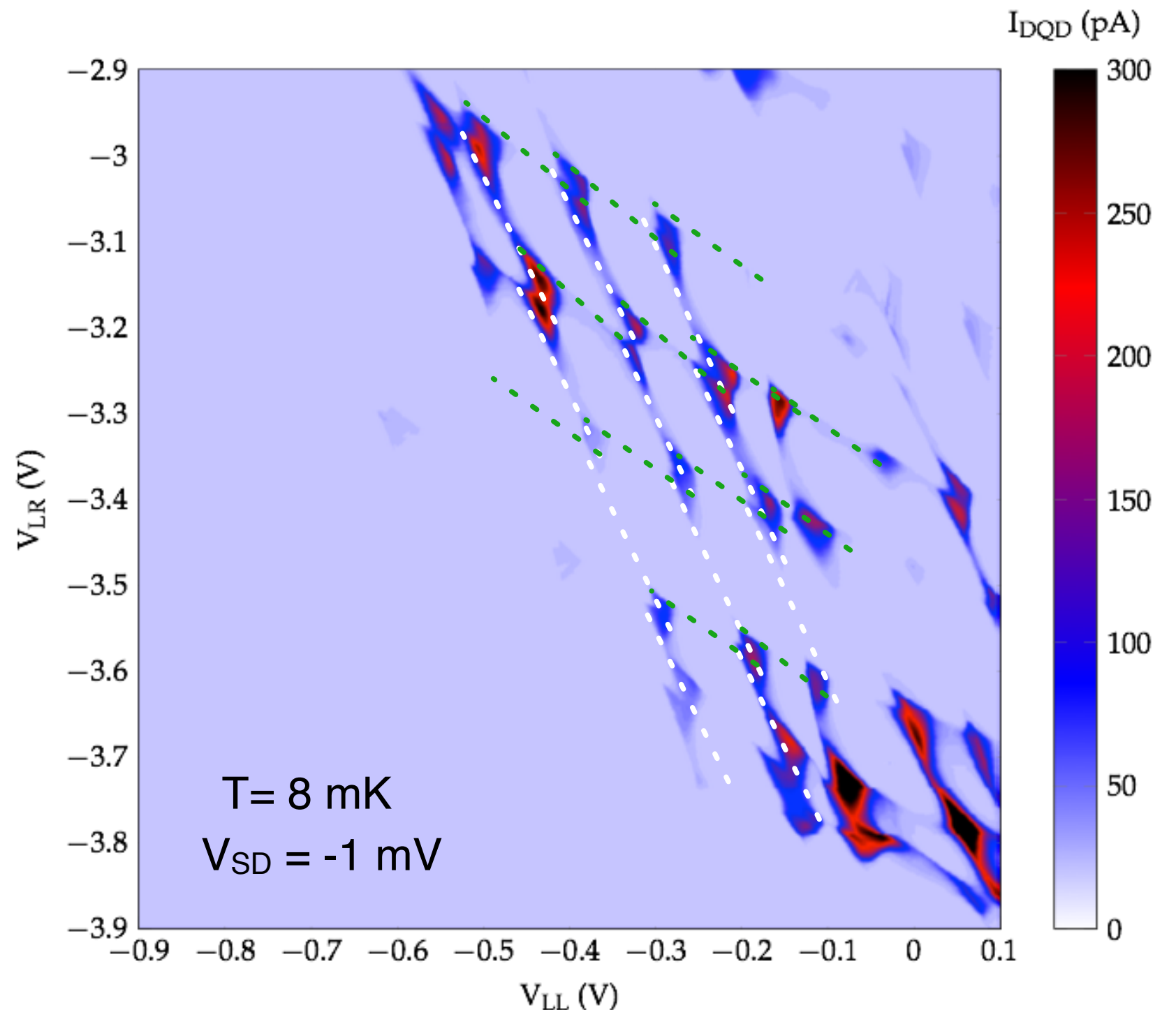
- Scanning the stability diagram along the green arrow, sweeping the SD bias
- Last diamond not closing for SD bias larger than 30 mV
- **Single electron regime**



Stability Diagram

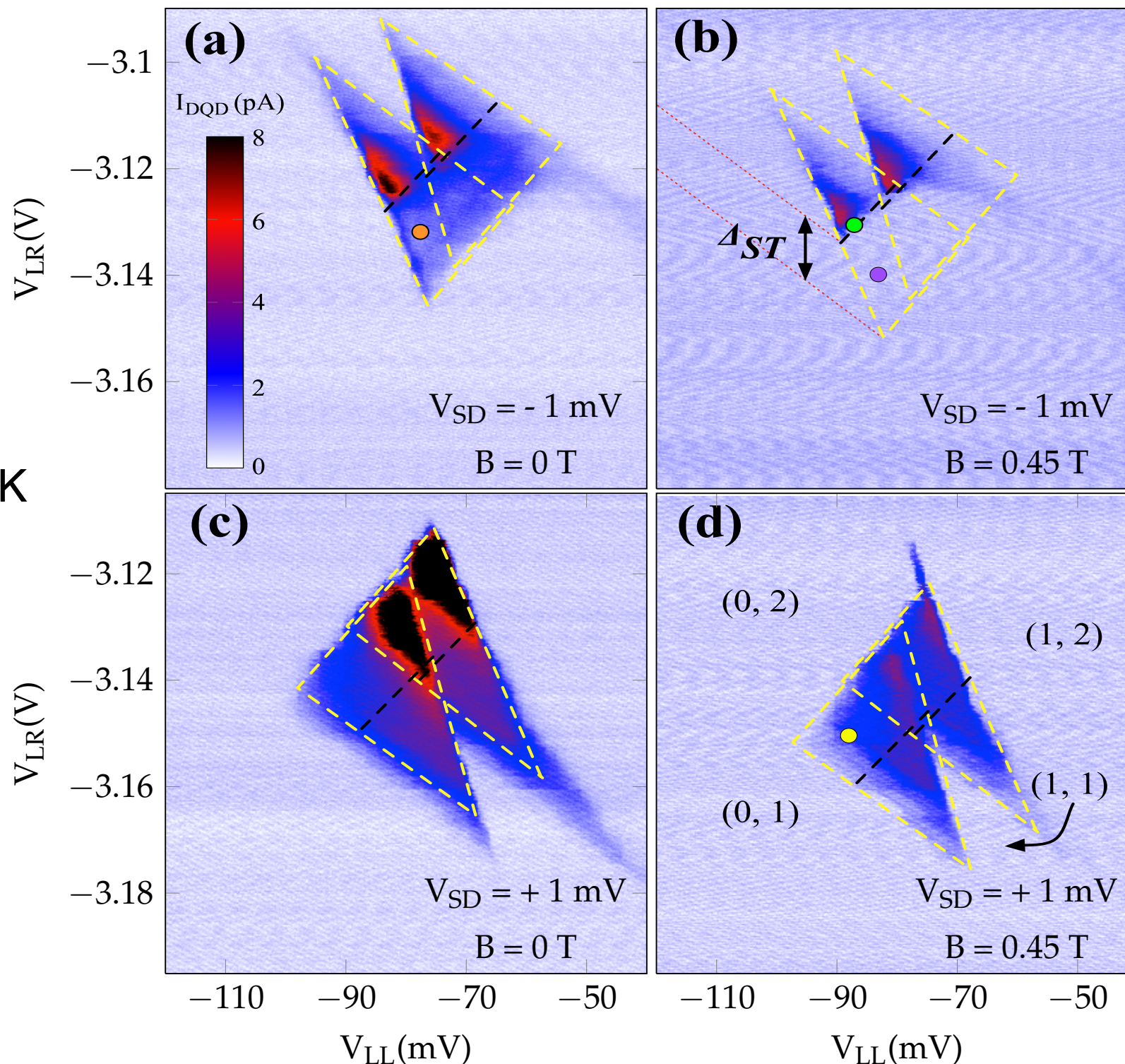
Characteristic energies	
E	2.3 ± 0.6 meV
E	2.3 ± 0.3 meV
$\triangle E$ left	0.3 ± 0.2 meV
$\triangle E$ right	0.3 ± 0.2 meV
E	0.3 ± 0.4 meV

- Lithographic double quantum dot



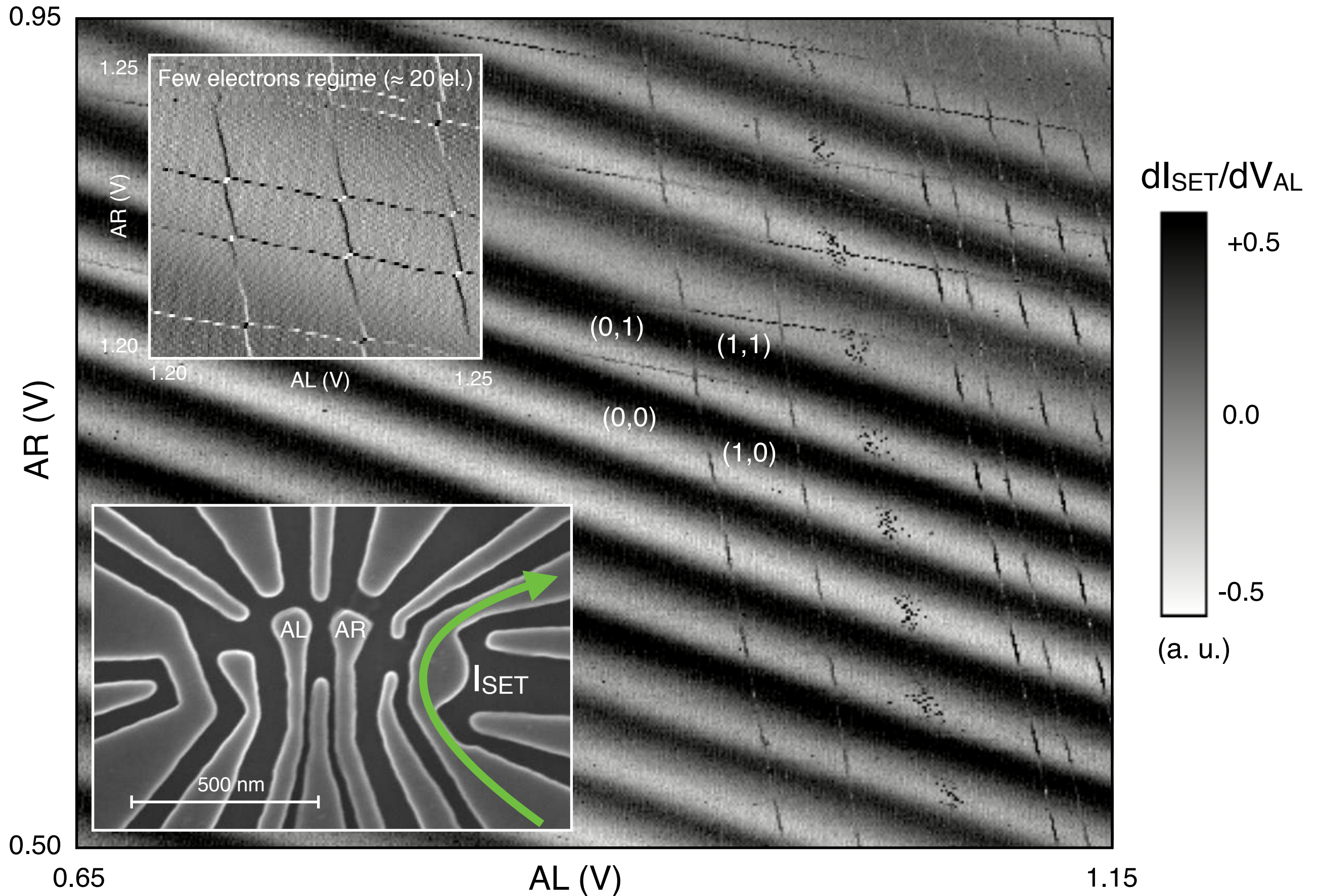
Pauli Spin Blockade

T = 8 mK



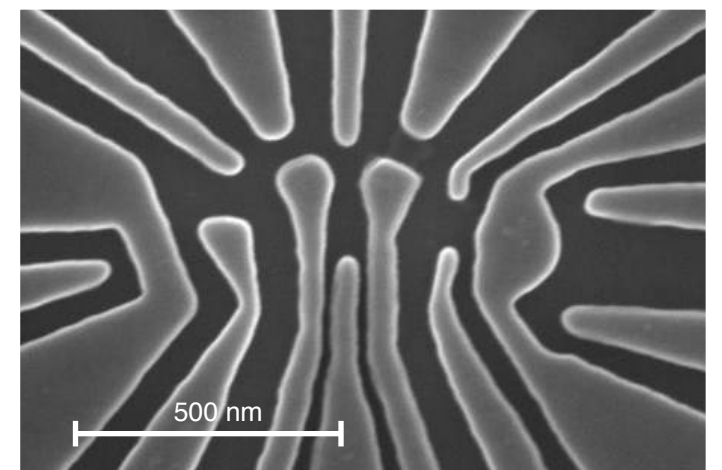
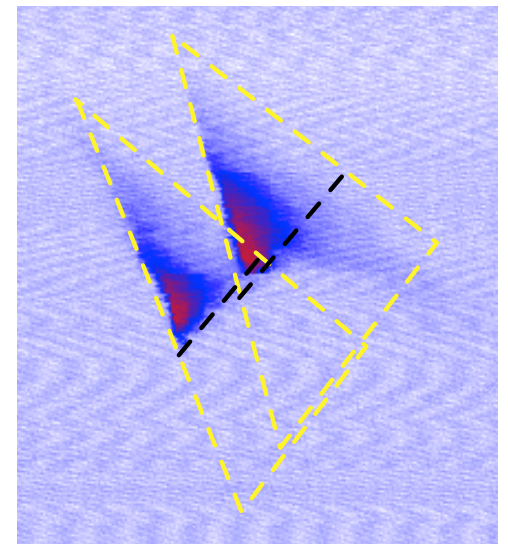
- In plane magnetic field
- Singlet-triplet separation: 0.4 meV
- Effective electron number only

New design: zero electrons



Conclusion

- Single-electron regime in a Si MOS DQD
- Lithographic double quantum dot:
 $E_{\text{add}} = 2.3 \text{ meV}$, $\Delta E = 0.3 \text{ meV}$
- Pauli Spin Blockade: $\Delta_{\text{ST}} = 0.4 \text{ meV}$
- Improved device: zero electron regime.



Thank you!